

# High-temperature optical constants, band-gap energies and in-situ growth monitoring of ZnO thin films

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## Our messages

In-situ ellipsometry is a versatile technique for optical monitoring of PLD-grown ZnO thin films.

Sample temperature calibration versus heater power can be easily done.

We report the high-temperature band-gap energies and optical constants of ZnO.

The ZnO growth rate depends on deposition time, causing vertical gradients of optical constants and likely changes in the thin film microstructure. This gradient cannot be resolved anymore from a post-growth ex-situ ellipsometry experiment.

## Goals: in-situ Ellipsometry control of novel flexible solar cells

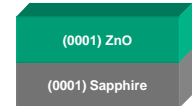
In-situ monitoring and feed-back control of CuInSe<sub>2</sub> (Cu(In,Ga)Se<sub>2</sub>) and ZnO (Zn(Cd,Mg)O) thin film growth

Here: ZnO thin films

- Attractive for developing short-wavelength optical devices: wide band gap (~3.37 eV) and high exciton binding energies band gap engineering: Zn<sub>1-x</sub>(Cd,Mg)<sub>x</sub>O compound thin films
- Applications as transparent conducting oxide: front contacts for flexible solar cells

Future task: CuInSe<sub>2</sub>/ZnO heterostructures

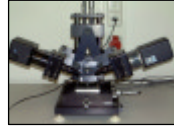
- CIGS absorber layers for high-efficient solar cells: New generation of thin film solar cell structures on flexible polymer sheets
- Band gap engineering: Cu<sub>1-x</sub>(In,Ga)<sub>x</sub>Se<sub>2</sub> compound thin films



## In-situ Ellipsometer setups

M-2000VI in-situ Ellipsometer (J.A. Woollam Co.)

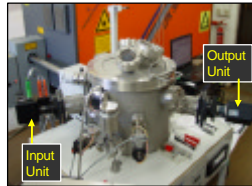
- polarizer-sample-rotating-compensator-analyzer
- spectral range: 0.75-3.345 eV
- diode-array detector
- ex-situ mode possible
- typical measurement time: 0.5 ... 2s



PLD chamber setup

Pulsed-Laser-Deposition

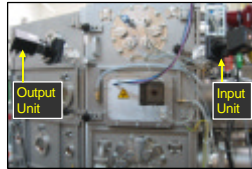
- Growth of wurtzite-type ZnO and Zn<sub>1-x</sub>(Cd,Mg)<sub>x</sub>O compound films on a-, c-, and r- plane Al<sub>2</sub>O<sub>3</sub>
- KrF excimer laser ablation
- Optical ports at AOI of 70°



Roll-coater setup, Solarion GmbH, Leipzig

Ion-Beam-Deposition

- Growth of Cu<sub>1-x</sub>(In,Ga)<sub>x</sub>Se<sub>2</sub>-based solar-cells on flexible polymer sheets
- Optical access ports at AOI of 43° and 67°

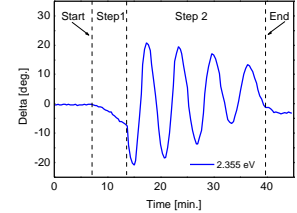


## PLD growth of (0001) ZnO thin film on (0001) Al<sub>2</sub>O<sub>3</sub>

Two-step-growth-process<sup>2</sup>

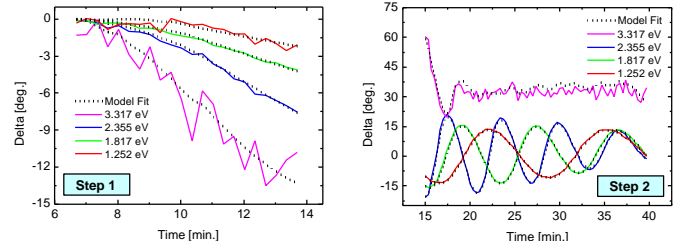
Growth Conditions

- Step 1** O<sub>2</sub>-Pressure = 3\*10<sup>-4</sup> mbar  
400 Laser pulses / 1 Hz/600 mJ
- Step 2** O<sub>2</sub>- Pressure = 1\*10<sup>-2</sup> mbar  
16000 Laser pulses / 10 Hz/600 mJ
- T=1053 K



<sup>2</sup> E. M. Kaidashev et al., Appl. Phys. Lett. **82**, 3901 (2003).

In-situ data analysis: Virtual-Interface-Approach<sup>3</sup>



## PLD: temperature calibration

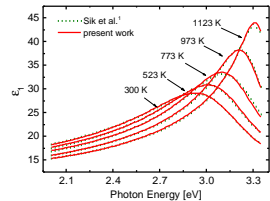
- SE-spectra of Si-wafer at different sample-heater power values
- Use of known temperature-dependent Si-optical constants<sup>1</sup>
- Calibration of the heater power to adjust the actual sample temperature

<sup>1</sup> J. Šik et al., J. Appl. Phys. **84**, 6291 (1998).

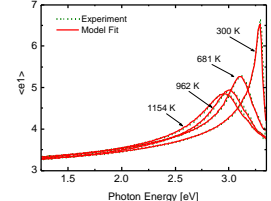
## High-temperature ZnO band gap

- Temperature-dependent ex-situ SE spectra of a bulk (0001) ZnO from 300 K to 1154 K
- Strong red-shift and splitting of the E<sub>A,B,C</sub> band-gap energies with temperature:
  - $dE_A/dT = -(7 \pm 1) \times 10^{-4}$  eV/K
  - $dE_B/dT = -(6 \pm 1) \times 10^{-4}$  eV/K
  - $dE_C/dT = -(5 \pm 1) \times 10^{-4}$  eV/K
- Linear increase of the optical constants

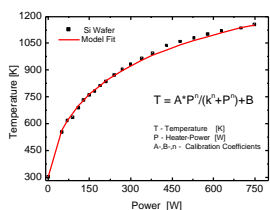
## Si $\epsilon_1$ at elevated temperatures



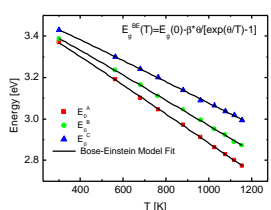
## ZnO $\langle \epsilon_1 \rangle$ at elevated temperatures



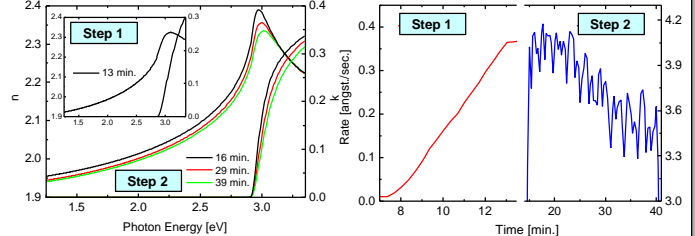
## Sample temperature vs. heater power



## ZnO band-gap energies

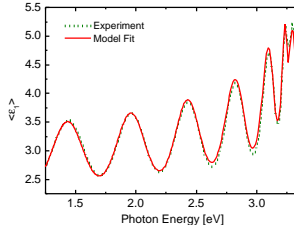


## In-situ data analysis results



<sup>3</sup> D. E. Aspnes et al., Appl. Phys. Lett. **57**, 2707 (1990).

## Ex-situ data analysis



## In Summary

In-situ: Virtual-Interface-Approach

- Step 1. Nucleation-zone thickness: 15 nm  
Growth-rate increases
- Step 2. Growth-rate decreases  
Optical constants change  
Total film thickness: 630 nm

Linear-growth-rate analysis

fails because the growth rates changes with time

Ex-situ-analysis

- Nucleation zone is not detectable
- Total film thickness: 634 nm
- Surface roughness: 4.7 nm
- Film-thickness-non-uniformity: 7.3%

## Conclusions

Ex-situ effective thickness in good agreement with actual thickness, but gradient due to growth-rate-change and nucleation zone cannot be resolved